

IN THE U.S. PATENT AND TRADEMARK OFFICE

In re application of

Pere ROCA I CABARROCAS et al.

Conf.

Application No. NEW NATIONAL PHASE

Group

Filed August 8, 2005

Examiner

TRANSISTOR FOR ACTIVE MATRIX DISPLAY AND A METHOD FOR PRODUCING
SAID TRANSISTOR

INFORMATION DISCLOSURE STATEMENT
(SUBMISSION CONCURRENT WITH THE
FILING OF A NEW PATENT APPLICATION)

Assistant Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

August 8, 2005

Sir:

Pursuant to 37 C.F.R. §§ 1.97 and 1.98, and in fulfillment of the duty of disclosure under 37 C.F.R. § 1.56, applicant(s) hereby submit(s) an Information Disclosure Statement for consideration by the Examiner.

I. LIST OF PATENTS, PUBLICATIONS OR OTHER INFORMATION

The patents, publications, or other information submitted for consideration by the Office are listed on PTO-1449, attached hereto.

II. COPIES

- ☒ Copies of the U.S. patents or publications are not submitted since the USPTO has waived their submission for applications filed after June 30, 2003.
- ☐ Submitted herewith is a legible copy of (i) each foreign patent; (ii) each publication or that portion which caused it to be listed; and (iii) all other information or that portion which caused it to be listed.
- ☒ This application is a National Phase of a PCT application. Some or all of the documents listed on the PTO-1449 are not enclosed because they were cited in the International Search Report and copies should have been forwarded from the International Search Authority pursuant to the trilateral agreement between the USPTO, EPO and JPO, or they are U.S. patents or U.S. published applications. If copies are needed, please contact the undersigned.

III. CONCISE EXPLANATION OF THE RELEVANCE
(check at least one box)

JP20 Rec'd PCT/PTO 08 AUG 2009

a. ☐ **DOCUMENTS IN THE ENGLISH LANGUAGE**

The attached non U.S. patents, non U.S. patent application publications, foreign publications, or other information in the English language do not require a statement of relevancy.

b. ☐ **DOCUMENTS NOT IN THE ENGLISH LANGUAGE**

A concise explanation of the relevance of all patents, publications, or other information listed that is not in the English language is as follows:

c. ☒ **FOREIGN SEARCH REPORT OR ACTION**

An English language version of the search report or action that indicates the degree of relevance found by the foreign office is attached, thereby satisfying the requirement for a concise explanation. See MPEP 609(A)(3).

d. ☐ **OTHER**

The following additional information is provided for the Examiner's consideration.

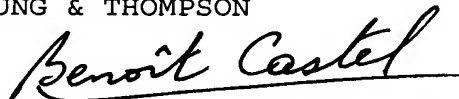
FEES

This Information Disclosure Statement is being filed concurrently with the filing of a new patent application; therefore, no fee is required.

If The Examiner has any questions concerning this IDS, he/she is requested to contact the undersigned.

Respectfully submitted,

YOUNG & THOMPSON



Benoit Castel, Reg. No. 35,041
745 South 23rd Street
Arlington, VA 22202
Telephone (703) 521-2297
Telefax (703) 685-0573
(703) 979-4709

BC/gw

Enclosures: ☒ Form PTO-1449(s)
☒ Documents
☒ Foreign Search Report
☐ Other: _____

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

Attorney Docket No.:

0510-1120

Application No.:

10/5/44787
NEW NATIONAL PHASE

Applicant:

Pere ROCA I CABARROCAS et al.

Filing Date:

August 8, 2005

Group Art Unit:

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing date (if appropriate)
	5,686,349	11/11/1997	NAKATA			
	6,017,779	1/25/2000	MIYASAKA			
	6,078,059	6/20/2000	NAKATA			

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	EP 0 609 867	8/10/1994	EUROPE				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	ROCA I CABARROCAS P ET AL: "STABLE MICROCRYSTALLINE SILICON THIN-FILM TRANSISTORS PRODUCED BY THE LAYER-BY-LAYER TECHNIQUE" JOURNAL OF APPLIED PHYSICS, AMERICAN INSTITUTE OF PHYSICS. NEW YORK, US, vol. 86, no. 12, 15 December 1999 (1999-12-15), pages 7079-7082, XP000928312 ISSN: 0021-8979 cited in the application page 7079
	YOUNG-BAE PARK ET AL: "EFFECT OF HYDROGEN PLASMA PRECLEANING ON THE REMOVAL OF INTERFACIAL AMORPHOUS LAYER IN THE CHEMICAL VAPOR DEPOSITION OF MICROCRYSTALLINE SILICON FILMS ON SILICON OXIDE SURFACE" APPLIED PHYSICS LETTERS, AMERICAN INSTITUTE OF PHYSICS. NEW YORK, US, vol. 68, no. 16, 15 April 1996 (1996-04-15), pages 2219-2221, XP000585161 ISSN: 0003-6951 page 2219

EXAMINER:

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

* English language abstract provided for the Examiner's convenience

BC/gw

Y&T August 8, 2005